

AMENDMENTS TO THE SPECIFICATION

On page 7, please replace the sixth and seventh (last) paragraphs (paragraphs [20] and [21]), with the following rewritten paragraph:

[20] The polishing composition according to any one of [4] to [19] above, wherein said ~~inorganic~~ acids is at least one species selected from the group consisting of sulfuric acid, phosphoric acid, phosphonic acid, ~~and~~ nitric acid. ~~—[21] The polishing composition according to [19] above, wherein said carboxylic acids is at least one species selected from the group consisting of~~ formic acid, acetic acid, propionic acid, butyric acid, valeric acid, 2-methylbutyric acid, n-hexanoic acid, 3,3-dimethylbutyric acid, 2-ethylbutyric acid, 4-methylpentanoic acid, n-heptanoic acid, 2-methylhexanoic acid, n-octanoic acid, 2-ethylhexanoic acid, benzoic acid, glycolic acid (hydroxyacetic acid), salicylic acid, glyceric acid, oxalic acid, malonic acid, succinic acid, glutaric acid, adipic acid, pimelic acid, maleic acid, phthalic acid, malic acid, tartaric acid, citric acid, lactic acid, nicotic acid, quinaldinic acid, and anthranilic acid.

On page 8, please replace the first full paragraph (paragraph [22]), with the following amended one:

~~[22]~~[21] The polishing composition according to any one of ~~[1]~~[4] to ~~[21]~~[20] above, wherein said base is at least one species selected from the group consisting of ammonia; sodium hydroxide; potassium hydroxide; potassium carbonate; potassium hydrogencarbonate; ammonium hydrogencarbonate; ~~alkylmonoamines; allylamine; 2-ethylhexylamine; cyclohexylamine, benzylamine, and furfurylamine; monoamines having a hydroxyl group; diamines; and polyamines~~ methylamine, ethylamine, propylamine, isopropylamine, butylamine,

isobutylamine, t-butylamine, amylamine, allylamine, 2-ethylhexylamine, cyclohexylamine, benzylamine, furfurylamine; o-aminophenol, ethanolamine, 3-amino-1-propanol, 2-amino-1-propanol; ethylenediamine, diethylenetriamine, triethylenetetramine, tetraethylenepentamine, pentaethylenehexamine, o-phenylenediamine, trimethylenediamine, 1,2-diaminopropane, 2,2-diamino-di-n-propylamine, 2-methyl-2-(2-benzylthioethyl)ethylenediamine, 1,5-diamino-3-pentanol, 1,3-diamino-2-propanol, xylenediamine, bisaminopropylpolyalkylene ether; polyallylamine and polyethyleneimine.

On page 8, please replace the second paragraph ([23]), with the following amended one:

[23][22] The polishing composition according to any one of [4] to [22][21] above, wherein said oxidizing agent is at least one species selected from the group consisting of oxygen, hydrogen peroxide, ozone, alkyl peroxides, peracids, permanganate salts, persulfate salts, polyoxo acids, hypochlorite salts, and periodate salts.

On page 8, please replace the third paragraph ([24]), with the following amended one:

[24][23] The polishing composition according to any one of [8] to [23][22] above, wherein said abrasive is formed of at least one species selected from the group consisting of silica, cerium oxide, aluminum oxide, aluminum hydroxide, titanium dioxide, and organic abrasive.

On page 8, please replace the fourth paragraph ([25]), with the following amended one:

[25][24] The polishing composition according to any one of [10] to [24][23] above, wherein said surfactant is at least one species selected from the group consisting of anionic surfactants, cationic surfactants, nonionic surfactants, and ampholytic surfactants.

On page 8, please replace the fifth paragraph ([26]), with the following amended one:

[26][25] The polishing composition according to any one of [10] to [25][24] above, wherein said surfactant is an alkylaromatic-sulfonic acid or a salt thereof.

On page 8, please replace the sixth paragraph ([27]), with the following amended one:

[27][26] The polishing composition according to any one of [12] to [26]25 above, wherein said compound having two or more azole moieties in its molecule is an azole polymer having a vinyl group.

On page 8, please replace the seventh paragraph ([28]), with the following amended one:

[28][27] The polishing composition according to [12] to [27][26] above, wherein said compound having two or more azole moieties in its molecule is a polymer having a mass average molecular mass of 2,000 to 500,000.

Please replace the paragraph bridging pages 8 and 9 ([29]), with the following amended one:

[29][28] The polishing composition according to any one of [13] to [28][27] above, wherein said amino acid is at least one species selected from the group consisting of glycine, alanine, β -alanine, 2-aminobutyric acid, norvaline, valine, leucine, norleucine, isoleucine, allo-isoleucine, phenylalanine, proline, sarcosine, ornithine, lysine, taurine, serine, threonine, allo-threonine, homoserine, tyrosine, 3,5-diiodo-tyrosine, β -(3,4-dihydroxyphenyl)-alanine, thyroxine, 4-hydroxy-proline, cysteine, methionine, ethionine, lanthionine, cystathionine, cystine, cysteic acid, aspartic acid, glutamic acid, S-(carboxymethyl)-cysteine, 4-aminobutyric acid, asparagine, glutamine, azaserine, arginine, canavanine, citrulline, δ -hydroxy-lysine, creatine, kynurenine, histidine, 1-methyl-histidine, 3-methyl-histidine, ergothioneine, and tryptophan.

Please replace the first full paragraph on page 9 ([30]), with the following amended one:

[30][29] The polishing composition according to any one of [15] to [29][28] above, wherein said compound having one azole moiety in its molecule is at least one species selected from the group consisting of benzimidazole-2-thiol, 2-[2-(benzothiazolyl)]thiopropionic acid, 2-[2-(benzothiazolyl)]thiobutyric acid, 2-mercaptobenzothiazole, 1,2,3-triazole, 1,2,4-triazole, 3-amino-1H-1,2,4-triazole, benzotriazole, 1-hydroxybenzotriazole, 1-dihydroxypropylbenzotriazole, 2,3-dicarboxypropylbenzotriazole, 4-hydroxybenzotriazole, 4-

carboxyl-1H-benzotriazole, 4-methoxycarbonyl-1H-benzotriazole, 4-butoxycarbonyl-1H-benzotriazole, 4-octyloxycarbonyl-1H-benzotriazole, 5-hexylbenzotriazole, N-(1,2,3-benzotriazolyl-1-methyl)-N-(1,2,4-triazolyl-1-methyl)-2-ethylhexylamine, tolyltriazole, naphthotriazole, benzimidazole, tetrazole, hydroxybenzotriazole, and carboxybenzotriazole.

Please replace the second full paragraph on page 9 ([31]), with the following amended one:

[31][30] A composition which forms the polishing composition as set forth in any one of [1] to [30][29] above by dilution.

Please replace the paragraph bridging pages 9 and 10 ([32]), with the following amended one:

[32][31] A kit comprising a plurality of compositions, which forms the polishing composition as set forth in any one of [1] to [30][29] above by (i) mixing or (ii) mixing and diluting said plurality of compositions.

Please replace the first full paragraph on page 10 ([33]), with the following amended one:

[33][32] A polishing method, characterized by comprising polishing, by use of the polishing composition as recited in any one of [1] to [30][29] above, a metal film provided on a substrate having trenches such that the metal film fills the trenches so as to provide a planarized surface.

Please replace the second full paragraph on page 10 ([34]), with the following amended one:

[34][33] The polishing composition according to [33][32] above, wherein said metal film is of copper or an alloy containing copper.

Please replace the third full paragraph on page 10 ([35]), with the following amended one:

[35][34] The polishing composition according to [34][33] above, wherein said metal film is stacked with at least two layers: a barrier layer and a metal wiring layer.

Please replace the fourth full paragraph on page 10 ([36]), with the following amended one:

[36][35] The polishing composition according to [35][34] above, wherein said barrier layer is formed of at least one species selected from the group consisting of tantalum, tantalum alloy, tantalum nitride, titanium, and titanium alloy.

Please replace the fifth full paragraph on page 10 ([37]), with the following amended one:

[37][36] A method for using the composition as set forth in [31][30] above.

Please replace the sixth full paragraph on page 10 ([38]), with the following amended one:

[38][37] A method for using the kit as set forth in [32][31] above as a composition for transportation or storage.

Please replace the paragraph bridging pages 11 and 12 with the following amended one:

Examples of the aforementioned phosphate ester include octyl phosphate, decyl phosphate, lauryl phosphate, myristyl phosphate, cetyl phosphate, stearyl phosphate, secondary alkyl (av. C13) phosphate, 2-ethylhexyl phosphate, oleyl phosphate, monostearyl glyceryl ether phosphate, monocetyl glyceryl ether phosphate, monooleyl glyceryl ether phosphate, isostearyl glyceryl ether phosphate, polyoxyethylene octyl ether phosphate, polyoxyethylene decyl ether phosphate, polyoxyethylene lauryl ether phosphate, polyoxyethylene myristyl ether phosphate, polyoxyethylene cetyl ether phosphate, polyoxyethylene stearyl ether phosphate, polyoxyethylene secondary alkyl (av. C13) ether phosphate, polyoxyethylene 2-ethylhexyl ether phosphate, polyoxyethylene 2-oleyl ether phosphate, and polyoxyethylene nonylphenyl ether phosphate. Of these, C8 to C18 alkyl phosphates such as octyl phosphate, lauryl phosphate, and stearyl phosphate; and phosphate esters having an oxyethylene chain such as polyoxyethylene lauryl ether phosphate and polyoxyethylene secondary alkyl (av. C13) ether phosphate are preferred.

Please replace the second full paragraph on page 15, with the following amended one:

In the present invention, any of anionic surfactants, cationic surfactants, and nonionic surfactants may be employed. Examples of the cationic surfactants include aliphatic amines or salts thereof and aliphatic ammonium salts. Examples of the anionic surfactants include fatty acid soap; alkyl ether carboxylic acids and salts thereof; sulfonic acid compounds such as α -olefinsulfonic acids and salts thereof, alkylbenzenesulfonic acids and salts thereof, and alkylnaphthalenesulfonic acids and salts thereof; and sulfate ester compounds (e.g., higher alcohol sulfate esters, and alkyl(phenyl) ether sulfuric acids and salts thereof). Examples of the non-ionic surfactants include ~~ester species~~ether species (e.g., polyoxyethylene alkyl ethers), ether-ester species (e.g., glycerin ester polyoxyethylene ethers), and ester species (e.g., polyethylene glycol fatty acid esters, glycerin esters, and sorbitan esters). Of these, sulfonate compound surfactants are preferred, with alkylaromatic sulfonic acids having an alkyl group and salts thereof being more preferred.

Please replace the first full paragraph on page 21, with the following amended one:

The polishing pad employed in the present invention is generally made of non-woven fabric or polyurethane foam. Most polishing pads have grooves so as to accelerate ~~polishing~~polishing rate and to facilitate discharge of a polishing slurry. Examples of such grooved polishing pads include a polishing pad having grooves in the lengthwise and widthwise directions (XY groove) and a polishing pad having concentric grooves (K groove). The polishing composition of the present invention is applicable to any of these polishing pads.

Preliminary Amendment
Based on PCT/JP2004/017317

Polishing pads are generally dressed by means of a diamond dresser so as to prevent clogging and to perform reliable polishing. In the present, any conventionally known dressing method may be employed.